	Application No.	Applicant(s)
Notice of Allowability	09/901,438	HASEGAWA ET AL.
	Examiner	Art Unit
	Christopher R. Magee	2653
The MAILING DATE of this communication app. All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	pears on the cover sheet with	s application. If not included ation will be mailed in due course. THIS
1. This communication is responsive to <u>restriction election of</u>	<u>f 12/27/2004</u> .	
2. The allowed claim(s) is/are <u>17-46</u> .		
3. \boxtimes The drawings filed on <u>09 July 2001</u> are accepted by the Ex	xaminer.	
 4. Acknowledgment is made of a claim for foreign priority unal All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	e been received. e been received in Application N	lo
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		eply complying with the requirements
5. A SUBSTITUTE OATH OR DECLARATION must be subminformal PATENT APPLICATION (PTO-152) which give		
6. CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the state of the sheet.	son's Patent Drawing Review (P - 's Amendment / Comment or in t 1.84(c)) should be written on the di	the Office action of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT		
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/C Paper No./Mail Date 7/9/2001 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	6. ☐ Interview Sumn Paper No./Mail 08), 7. ☐ Examiner's Ame	nal Patent Application (PTO-152) nary (PTO-413), I Date endment/Comment tement of Reasons for Allowance
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DETAILED ACTION

Election/Restrictions

1. Claims 1-16 and 47-78 are withdrawn from further consideration pursuant to 37 CFR

1.142(b), as being drawn to a nonelected species, there being no allowable generic or linking

claim. Applicant timely traversed the restriction (election) requirement in the reply filed on

12/27/2004.

2. Applicant's election of Species B (claims 17-46) in the reply filed on 12/27/2004 is

acknowledged. Because applicant did not distinctly and specifically point out the supposed

errors in the restriction requirement, the election has been treated as an election without traverse

(MPEP § 818.03(a)).

Priority

3. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Reasons for Allowance

- 4. Claims 17-46 are allowed (renumbered as 1-30, respectively).
- 5. The following is an examiner's statement of reasons for allowance:

This application is for an EXCHANGE COUPLING FILM AND
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MAGNETORESISTIVE ELEMENT USING THE SAME.

• Claim 17 specifies an exchange coupling film, which requires:

"wherein second imaginary line in the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer, the secondary imaginary lines each connecting the beam origin and a particular one of the diffraction spots which is given the same label in both the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer and which is located in a direction other than the layer thickness direction when viewed from the beam origin, are not coincident with each other."

Fukuzawa et al. (US 6,338,899 B1) show a diffraction diagram of the antiferromagnetic layer with a dispersion angle of half value width in the <111> direction [Fig. 20; col. 50, lines 58]. Fukuzawa et al. do not teach and/or suggest a second imaginary line in the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer, the secondary imaginary lines each connecting the beam origin and a particular one of the diffraction spots which is given the same label in both the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer and which is located in a direction other than the layer thickness direction when viewed from the beam origin, are not coincident with each other as claimed in the present invention.

Fuke et al. (US 5,976,713) show an electron beam diffraction pattern of the antiferromagnetic layer oriented in one plane [Figs. 8 and 9; col. 8, lines 46-50]. Fuke et al. do not teach and/or suggest a second imaginary line in the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer, the secondary imaginary lines each connecting the beam origin and a particular one of the diffraction spots which is given the same label in both the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer and which is located in a direction other than the layer thickness direction when viewed from the beam origin, are not coincident with each other as claimed in the present invention

Therefore, these features, in combination with other features of claim 17 are not anticipated by, nor made obvious over, the closest prior art of record Fukuzawa et al. (US 6,338,899 B1) and/or Fuke et al. (US 5,976,713).

• Claim 32 specifies an exchange coupling film, which requires:

"wherein a particular diffraction spot indicative of a particular crystal plane, located in a direction other than the layer thickness direction, appears only in one of the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer."

Fukuzawa et al. (US 6,338,899 B1) show a diffraction diagram of the antiferromagnetic layer with a dispersion angle of half value width in the <111> direction (Fig. 20; col. 50, lines 58). Fukuzawa et al. do not teach and/or suggest a particular diffraction spot indicative of a particular crystal plane, located in a direction other than the layer thickness direction, appears only in one of the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer as claimed in the present invention.

Fuke et al. (US 5,976,713) show an electron beam diffraction pattern of the antiferromagnetic layer oriented in one plane [Figs. 8 and 9; col. 8, lines 46-50]. Fuke et al. do not teach and/or suggest a particular diffraction spot indicative of a particular crystal plane, located in a direction other than the layer thickness direction, appears only in one of the diffraction diagrams of the antiferromagnetic layer and the ferromagnetic layer as claimed in the present invention.

Therefore, these features, in combination with other features of claim 32 are not anticipated by, nor made obvious over, the closest prior art of record Fukuzawa et al. (US 6,338,899 B1) and/or Fuke et al. (US 5,976,713).

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6. Any comments considered necessary by applicant must be submitted no later than the

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payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

Conclusion

7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Christopher R. Magee whose telephone number is (571) 272-

7592. The examiner can normally be reached on M-F, 8: 00 am-5: 30 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, William Korzuch can be reached on (571) 272-7589. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

March 19, 2005

Christopher R. Magee Patent Examiner

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CRM

CRAISA RENNER